

EAST Search History**EAST Search History (Prior Art)**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	407	immersion lithograph\$4 and (vibrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/16 11:47
L3	161011	("250").CLAS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/07/16 11:49
S1	954	(250/492.22).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/03/25 17:03
S2	9775	(250/492.1-492.3).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/03/25 17:04
S3	9775	(250/492.1-492.3).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/03/26 13:05
S4	86	\$3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 13:05

S5	36	S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 13:09
S6	33	S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 13:15
S7	24	S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 13:17
S8	9	S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp \$4 or isolat\$4 or minimiz \$4 or prevent\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 13:28

S9	9	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp \$4 or isolat\$4 or minimiz \$4 or prevent\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 13:30
S10	0	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp \$4 or isolat\$4 or minimiz \$4 or prevent\$4) and vibration with rais\$4 and vibration with low\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 13:34
S11	0	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp \$4 or isolat\$4 or minimiz \$4 or prevent\$4) and	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 13:34

		vibrat\$4 with rais\$4 and vibrat\$4 with low\$4				
S12	1	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp \$4 or isolat\$4 or minimiz \$4 or prevent\$4) and vibrat\$4 with (rais\$4 or low\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 13:35
S13	1	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp \$4 or isolat\$4 or minimiz \$4 or prevent\$4) and vibrat\$4 with (rais\$4 or low\$4) and liquid	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 13:38
S14	0	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 13:54

		(move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp\$4 or isolat\$4 or minimiz\$4 or prevent\$4) and vibrat\$4 with (rais\$4 or low\$4) and liquid and ("3" or three) with degree\$4 with freedom				
S15	1	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate and liquid same (optical with (column or body))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 15:18
S16	0	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate and liquid with liquid with (optical with (column))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:28
S17	0	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate and liquid with (optical with (column))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:29
S18	0	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate and liquid with (optical with (column or body))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:30

S19	1	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate and dry with immersion	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:31
S20	4	@ad<"20050112" and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate and dry with immersion	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:32
S21	4	@ad<"20050112" and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate and liquid with (column)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:33
S22	0	@ad<"20050112" and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate and liquid with (optical with column)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:33
S23	1	@ad<"20050112" and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate and liquid with (optical with (body or column))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:33

S24	0	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp \$4 or isolat\$4 or minimiz \$4 or prevent\$4) and vibrat\$4 with (rais\$4 or low\$4) and abnormal\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:42
S25	1	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp \$4 or isolat\$4 or minimiz \$4 or prevent\$4) and vibrat\$4 with (rais\$4 or low\$4) and situation	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:43
S26	1	@ad<"20050112" and S3 and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:47

		\$4 or isolat\$4 or minimiz \$4 or prevent\$4) and vibrat\$4 with (rais\$4 or low\$4) and (situation or problem\$4 or abnormalit \$4 or issue)				
S27	22	@ad<"20050112" and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp \$4 or isolat\$4 or minimiz \$4 or prevent\$4) and vibrat\$4 with (rais\$4 or low\$4) and (situation or problem\$4 or abnormalit \$4 or issue)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:48
S28	0	@ad<"20050112" and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and vibrat\$4 with (damp \$4 or isolat\$4 or minimiz \$4 or prevent\$4) and vibrat\$4 with (rais\$4 or low\$4) and (situation or problem\$4 or abnormalit \$4 or issue) and earthquake	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:50

S29	1	@ad<"20050112" and pattern\$4 same mask same substrate and stage and detect\$4 with stage with (locat\$4 or posit\$4 or place\$4 or point\$4) and stage with substrate with (hold\$4 or attach\$4 or secur\$4 or grip\$4 or fix\$4) and stage with perpendicular and stage with axis with (optical or beam) with (move\$4 or accelerat\$4 or speed\$4 or velocity) and earthquake	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 16:50
S30	1	(US-20070146663-\$).did.	US-PGPUB	ADJ	ON	2008/03/26 18:44
S31	1	(US-6654095-\$).did.	USPAT	ADJ	ON	2008/03/26 18:51
S32	5	S12 or S13 or S15 or S19 or S23 or S25 or S26 or S29 or S30 or S31	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/26 18:54
S33	2	("20070164234").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/07/17 16:12
S34	496	@ad<"20040115" and immersion with lithograph \$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/12 17:25
S35	19	@ad<"20040115" and immersion with lithograph \$4 and (vibrat\$4) with (isolat\$4 or insulat\$4 or dampen\$4 or cancel\$6 or prevent\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/12 17:26

S37	11	(US-20020163629-\$ or US-20040114117-\$ or US-20040135468-\$ or US-20040189964-\$ or US-20050105070-\$ or US-20050122490-\$ or US-20050134827-\$ or US-20050140955-\$ or US-20050138988-\$ or US-20050164522-\$).did. or (US-5900354-\$).did.	US-PGPUB; USPAT	ADJ	ON	2010/07/12 17:27
S38	11	@ad<"20040115" and S37 and (vibrat\$4) with (isolat\$4 or insulat\$4 or dampen\$4 or cancel\$6 or prevent\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/12 17:27
S39	64	@ad<"20040115" and immersion with lithograph\$4 and (vibrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/13 12:13
S40	33	@ad<"20040115" and immersion NEAR3 lithograph\$4 and (vibrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/13 12:14
S41	27	@ad<"20040115" and immersion lithograph\$4 and (vibrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/13 12:14
S42	189	@ad<"20040115" and immersion lithograph\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/13 13:45

EAST Search History (Interference)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	391	immersion lithograph\$4 and (vibrat\$4)	US-PGPUB; USPAT; UPAD	ADJ	ON	2010/07/16 11:47
L4	115556	("250").CLAS.	US-PGPUB; USPAT; UPAD	OR	OFF	2010/07/16 11:49
L5	18	L4 AND immersion lithograph\$4 and (vibrat\$4)	US-PGPUB; USPAT; UPAD	ADJ	ON	2010/07/16 11:49

7/16/2010 12:09:45 PM

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